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AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the

application:

Listing of Claims:

Claim 1 (currently amended): A DC amplifier formed on a substrate of a

semiconductor integrated circuit, comprising

a differential amplification circuit including a p-channel MIS field-effect transistor and

an n-channel MIS field-effect transistor in which a projecting portion is formed by a silicon

substrate having a first crystal surface as a primary surface and a second crystal surface as a side

surface, terminated hydrogen on the silicon surface is removed in plasma atmosphere of an inert

gas, then a gate insulating film is formed on at least a part of a top surface and the side surface of

the projecting portion at a temperature at or lower than about 550°C in the plasma atmosphere, a

gate is formed on the gate insulating film, and a drain and a source are formed on both sides

enclosing the gate insulating film of the projecting portion, wherein

gate widths of a top surface and a side surface of the p-channel MIS field-effect transistor

and the n-channel MIS field-effect transistor are set such that the current drive capability of the

p-channel MIS field-effect transistor can be substantially equal to current drive capability of the

n-channel MIS field-effect transistor.

Claim 2 (original): The DC amplifier according to claim 1, wherein

a channel is formed on the first crystal surface of a top surface and the second crystal

surface of the side surface of the projecting portion, and the channel width of the MIS field-

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effect transistor is a total of a channel width of the top surface and a channel width of the side

surface.

Claim 3 (previously presented): The DC amplifier according to claim 1, wherein

the projecting portion has the top surface comprising a silicon surface (100), the side

surface comprising a silicon surface (110), and the source and drain are formed on the projecting

portion enclosing the gate and in left and right areas of the projecting portion of the silicon

substrate.

Claim 4 (previously presented): The DC amplifier according to claim 1, further

comprising first and second MIS field-effect transistors for performing differential amplification

on an input signal, and a third MIS field-effect transistor which is connected to a source or a

drain of the first and second MIS field-effect transistors and configures a constant current circuit.

Claim 5 (original): The DC amplifier according to claim 4, further comprising fourth

and fifth MIS field-effect transistors which are connected between a source or a drain of the first

and second MIS field-effect transistors and configure a constant current circuit as a load of the

first and second MIS field-effect transistors.

Claim 6 (currently amended): A semiconductor integrated circuit, comprising on a

same circuit substrate:

a circuit including a p-channel MIS field-effect transistor and an n-channel MIS field-

effect transistor in which a projecting portion is formed by a silicon substrate having a first

crystal surface as a primary surface and a second crystal surface as a side surface, terminated

hydrogen on the silicon surface is removed in plasma atmosphere of an inert gas, then a gate

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insulating film is formed on at least a part of the top surface and the side surface of the projecting

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portion at a temperature at or lower than about 550°C in the plasma atmosphere, a gate is formed

on the gate insulating film, and a drain and a source are formed on both sides enclosing the gate

insulating film of the projecting portion; and

a DC amplifier having a differential amplification circuit including the p-channel MIS

field-effect transistor or the n-channel MIS field-effect transistor, wherein

gate widths of a top surface and a side surface of the p-channel MIS field-effect transistor

and the n-channel MIS field-effect transistor are set such that the current drive capability of the

p-channel MIS field-effect transistor can be substantially equal to current drive capability of the

n-channel MIS field-effect transistor.

Claims 7-8 (canceled):

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